

鍍膜與奈米科技實驗室 Thin Films and Nanotechnology Laboratory

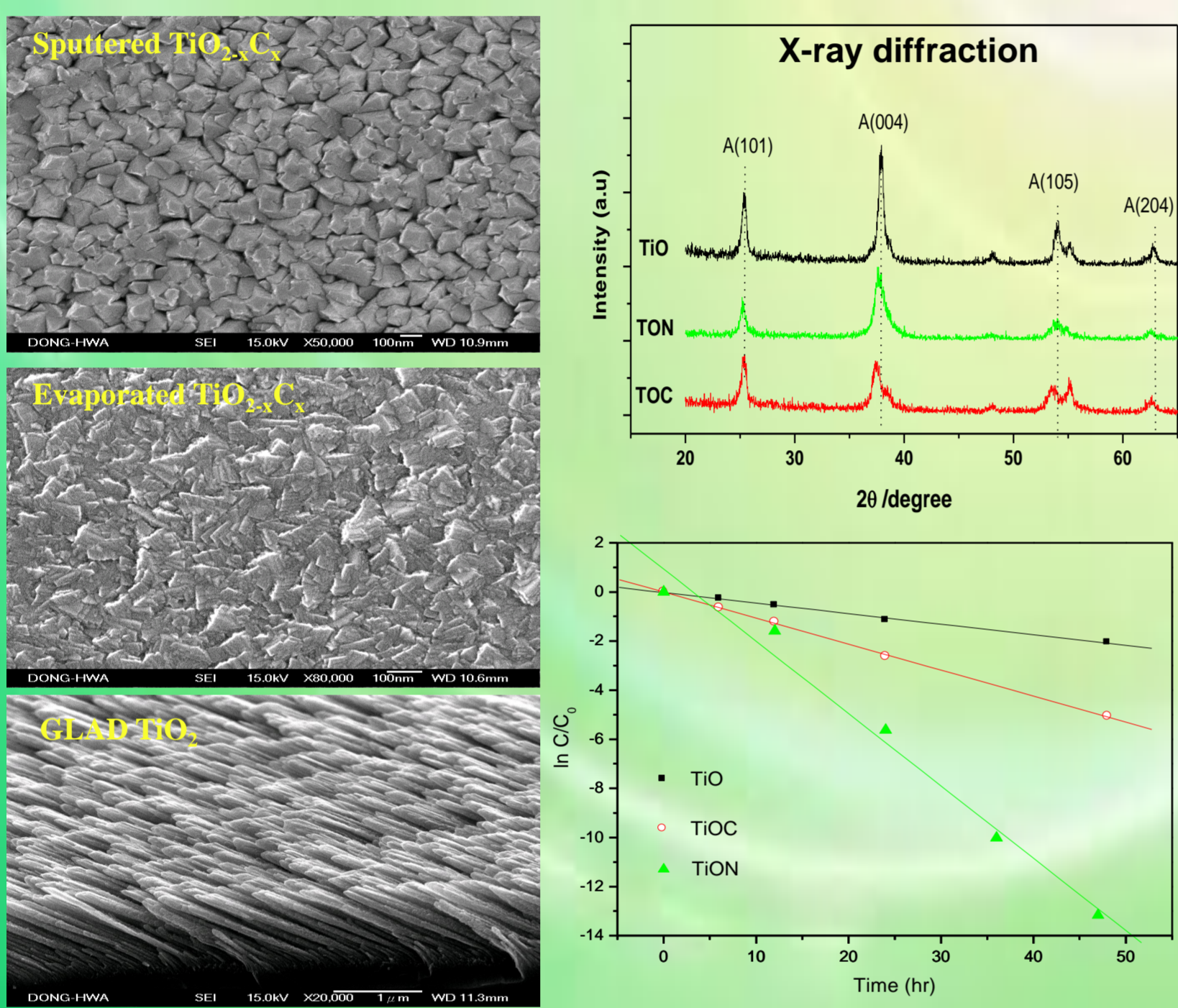


研究方向

- ☒ 奈米材料
- ☒ 光觸媒材料
- ☒ PVD與CVD薄膜
- ☒ 鍍膜及表面工程技術
- ☒ 硬及超硬材料
- ☒ 電子與光電材料

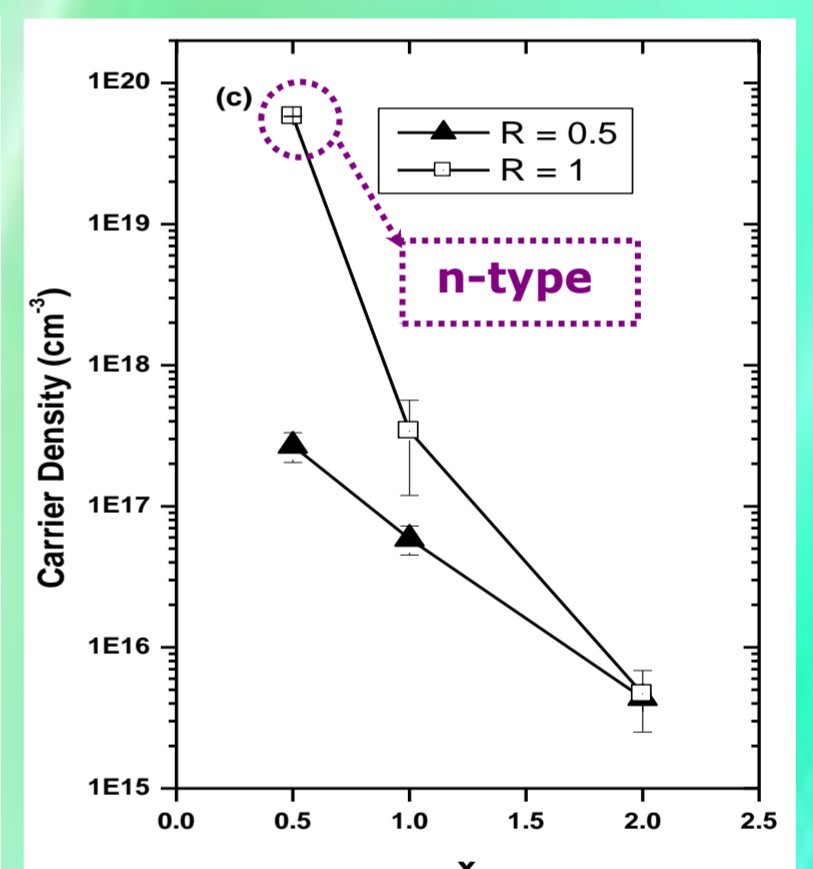
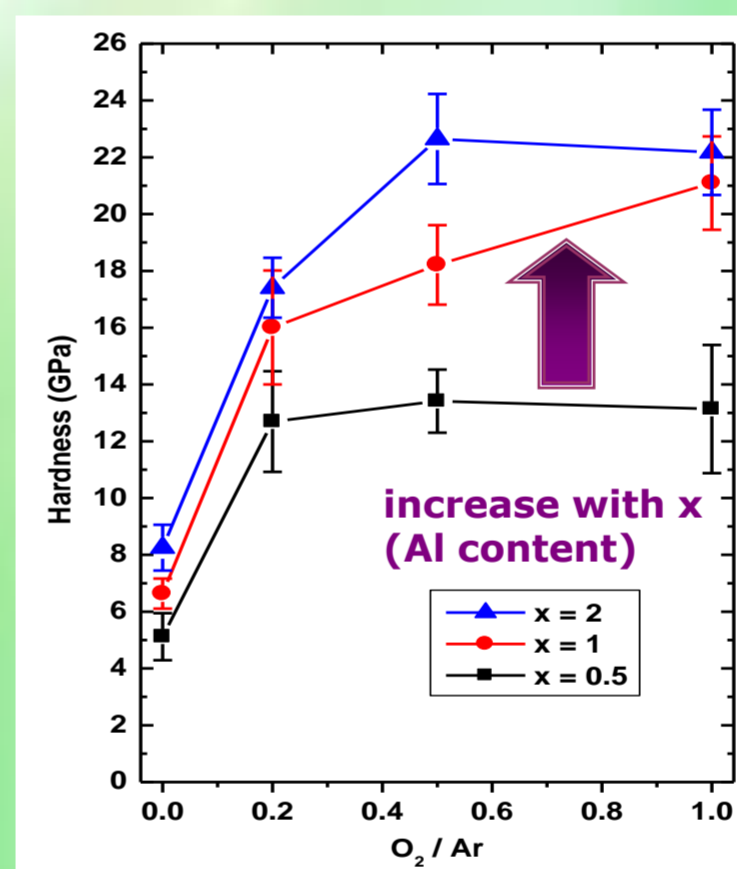
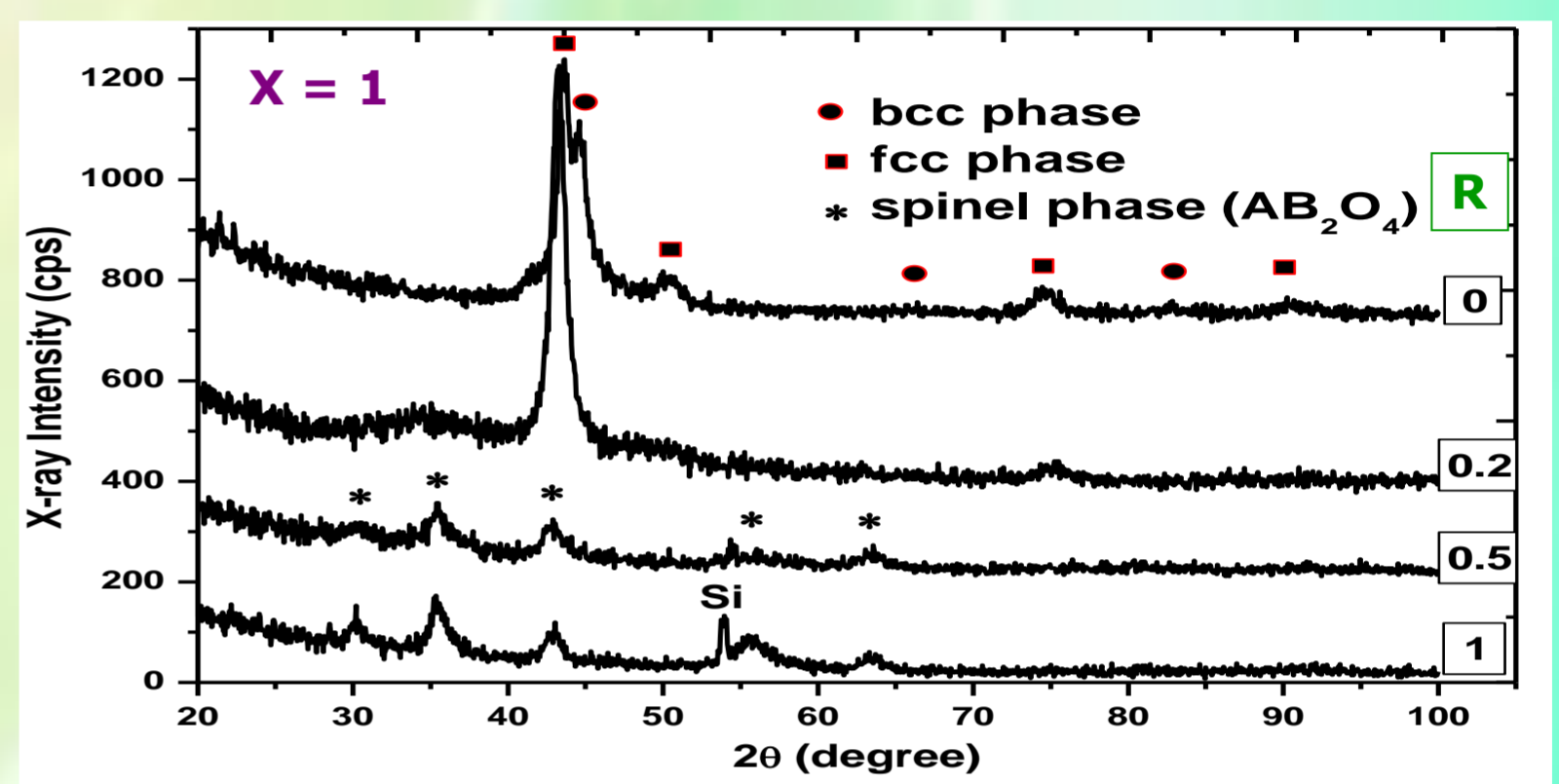
研究成果

Anion (C,N)-doped Titania Films

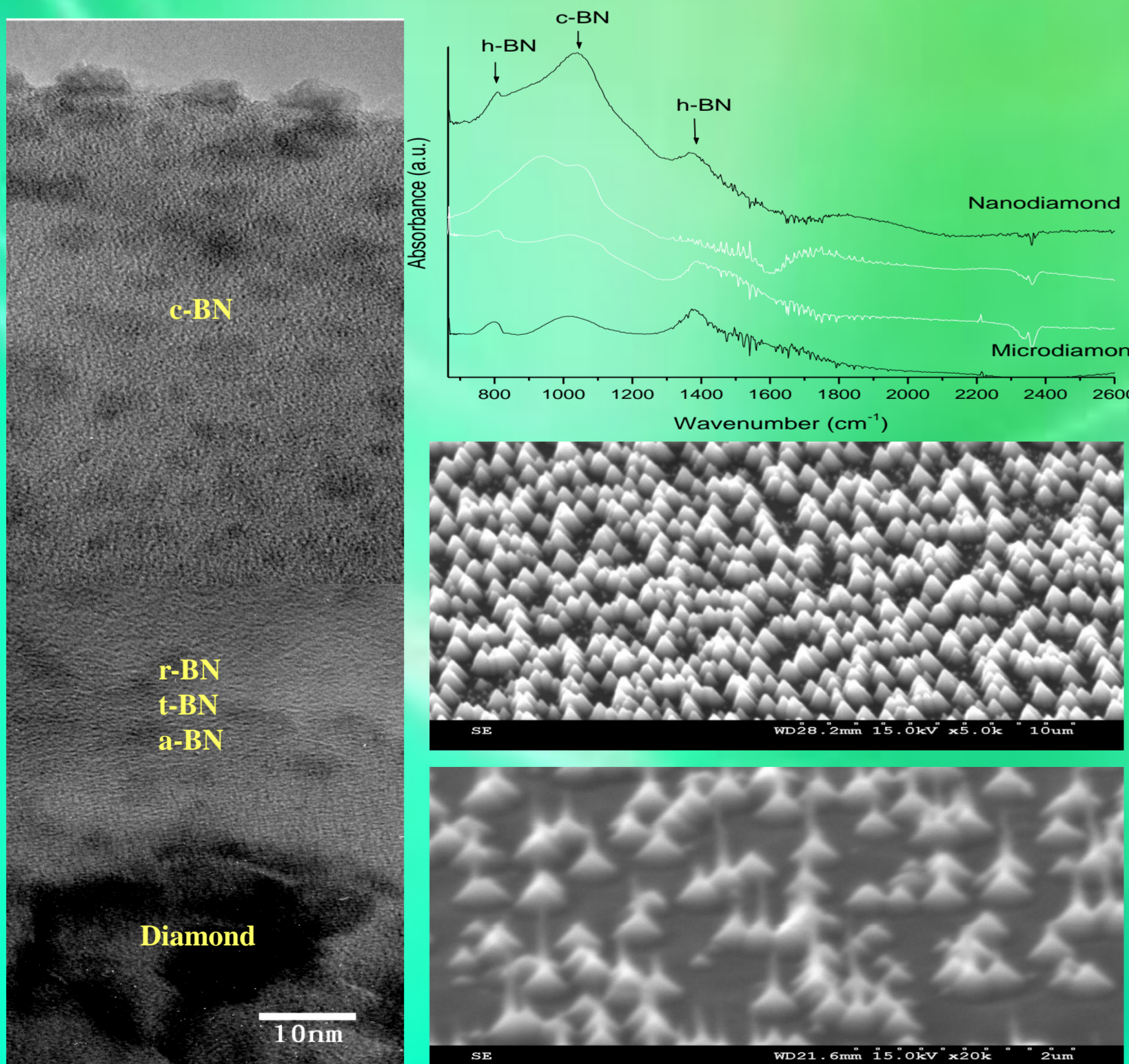


Film	Grain size (nm)	Contact angle after 60 min. visible illuminations (°)		Rate constant, K (hour ⁻¹)	Atomic percentage % (C or N)
		Initial	Final		
TiO	18	62	52	0.042	0.48 (C)
TiOC	16	48	06	0.105	1.25 (C)
TiON	16	54	03	0.274	5.50 (N)

Reactively Sputtered Al_xCoCrCuFeNi Oxide Films



MPCVD of BN Films and Nanostructures



Silver Nanowires

